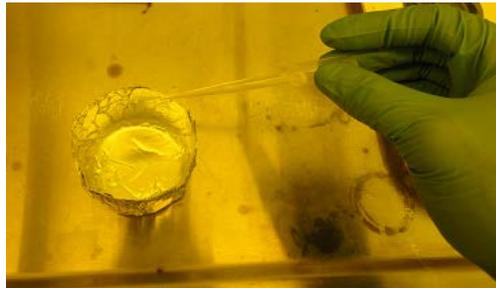


PROCEDURE FOR SILANIZATION OF SU-8/SILICON MASTER

Microfabrication Core Facility, Harvard Medical School

This process is intended to produce a passivation of the surfaces to aid release from PDMS and prevents the PDMS from adhering to the master.

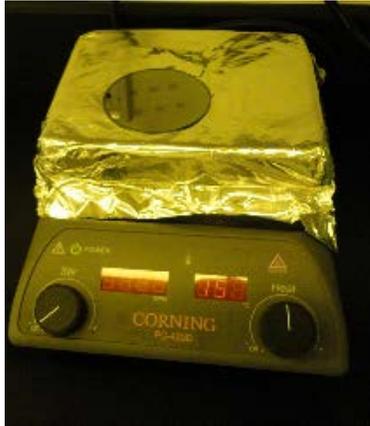
1. Clean the wafer (Pressurized nitrogen)
2. Inside the **fume hood**, use 2 drops (use plastic pipette) of the silanizing agent in an aluminum foil cap smaller than the wafer size.



3. Cover your foil cap containing the silinazing agent with the wafer and put them in the vacuum desiccator labeled as "silanization" to make the silanes form a monolayer on the surface of the master. Keep them for:
 - a. 10-15 min if you put the wafer right on top of the aluminum foil cap that contains the silane.
 - b. 30 min, if you place the wafer next to the aluminum foil cap which contains the silane.



4. Place the wafer on the hotplate in the **fume hood** 150°C for 10 mins to cure and evaporate the excessive silane.



NOTE: Trichloro perfluorooctyl silane should be always handled in the fume hood and kept away from water sources.